

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
ASMMC.008AUSAPPLICATION NO.  
08/452,844INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT  
Realmakers et al.FILING DATE  
December 3, 1999GROUP  
2825

## U.S. PATENT DOCUMENTS

| EXAMINER<br>INITIAL |   | DOCUMENT NUMBER | DATE     | NAME        | CLASS | SUBCLASS | FILING DATE<br>(IF APPROPRIATE) |
|---------------------|---|-----------------|----------|-------------|-------|----------|---------------------------------|
| RNR                 | 1 | 6,270,572       | 08/07/01 | Kim et al.  | —     | —        |                                 |
| RNR                 | 2 | 6,335,240       | 01/01/02 | Kim et al.  | —     | —        |                                 |
| RNR                 | 3 | 5,923,056       | 07/13/99 | Lee et al.  | —     | —        |                                 |
| RNR                 | 4 | 6,342,712       | 01/29/02 | Miki et al. | —     | —        |                                 |

| EXAMINER<br>INITIAL |   | OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)  |
|---------------------|---|---|
| RNR                 | 5 | Materro et al., "Effect of water dose on the atomic layer deposition rate of oxide thin films." Thin Solid Films 368 (2000), pgs. 1-7 |

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AUG 20 2003  
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|--|--------------------------|-----------------|-------------------|
| EXAMINER   | <i>DeWitt N. Reutgen</i> | DATE CONSIDERED | <i>10/20/2003</i> |
| *EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 809; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED; INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT. |                          |                 |                   |